## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applica	ation of:	)	PATENT APPLICATION
Inventors:	Jer-Shen Maa, Jong-Jan Lee, Douglas J. Tweet and Sheng Teng Hsu	)	
Serial No.:	Not Yet Assigned	)	Attorney Docket No. SLA 0749
Filed:	Herewith	)	3LA 0749
Title:	METHOD OF FORMING RELAXED SIGN LAYER	)	

Honorable Commissioner for Patents Alexandria, VA 22313-1450

## INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97

Sir:

Listed on attached Form PTO-1449 is information submitted pursuant to 37 C.F.R. §1.56. A copy of each listed publication is submitted herewith.

Applicant respectfully requests that the listed information be considered by

the Examiner and made of record in the above-identified application.

Respectfully bubynitte

Reg. No. 27,672

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1449A/PTO Rev. 10/95	•			Complete If Known	
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LIST OF PRIOR ART CITED				Filing Date	07-22-03
BY APPLICANT				First Named Inventor	Jer-shen Maa
				Group Art Unit	
(use as many sheets as necessary)			necessary)	Examiner Name	
Sheet	1	of	2	Attorney Docket No.	SLA.0749

	U.S. PATENT DOCUMENTS							
Examiner Initials	Cite No.¹	U.S. Patent Document Kind Number Co (if know	Name of Patentee or Applicant de <sup>2</sup> of Cited Document wn)	Date of Publication of Cited Document MM-DD-YY	Pages, Columns, Lines, Where Relevant Passages or Figures Appear			
		6,562,703 B1	Maa et al.	05-13-03				
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	FOREIGN PATENT DOCUMENTS								
Examiner Initials	Cite No.1	Foreign Patent Dcument	Name of Patentee or Applicant	Date of Publication of Cited Document	Pages, Columns, Lines, Where Relevant	T <sup>6</sup>			
		Office <sup>3</sup> Number <sup>4</sup> Kind Code <sup>5</sup>	of Cited Document	MM-DD-YY	Passages or Figures Appear				

	OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS					
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, country where published, source.	T²			
		G.F. CEROFOLINI et al., Hydrogen-related Complexes as the Stressing Species in High-fluence, Hydrogen-implanted, Single-crystal Silicon, Physical Review B, vol. 46, p. 2061 (1992)				
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		ADITYA AGARWAL et al., Efficient Production of Silicon-on-Insulator Films by Co-implantation of He <sup>+</sup> with H <sup>+</sup> , Proceedings of the 1997 IEEE International SOI Conference, p. 44, (1997).				

Examiner	Date	i
Signature	Considered	

Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

'Unique citation designation number. 'See attached Kinds of U.S. Patent Documents. 'Enter Office that issued the document, by the two letter code (WIPO Standard ST.3). 'For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. 'Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. 'Applicant is to place a check mark here if English language Translation is attached

1449A/PTO Rev. 10/95			S. Department of Commerce Patent and Trademark Office	Complete If Known		
Rev. 10/95			Tales and Trademark Office	Application Number		
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Sheet	2	of	2	Attorney Docket No.	SLA.0749	

		OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS	
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, country where published, source.	T²
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		H. TRINKAUS et al., Strain Relaxation Mechanism for Hydrogen-Implanted Si <sub>1-x</sub> Ge <sub>x</sub> /Si(100) Heterostructures, Appl. Phys. Lett., 76, 3552, (2000)	-
		K. RIM et al., Strained Si NMOSFETs for High Performance CMOS Technology, 2001 Symposium on VLSI Technology Digest of Technical Papers, p. 59, (IEEE 2001)	
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Signature		Considered	

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<sup>&</sup>lt;sup>1</sup>Unique citation designation number. <sup>2</sup>Applicant is to place a check mark here if English language Translation is attached.